	Application No.	Applicant(s)	
Alada CAH LUG	10/523,491	FEIRING ET AL.	
Notice of Allowability	Examiner	Art Unit	
	John S. Chu	1752	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in b) or other appropriate commu RIGHTS. This application is so	this application. If not include nication will be mailed in due of	d course. THIS
1. \boxtimes This communication is responsive to $2/21/07$.			
2. ⊠ The allowed claim(s) is/are <u>1-45</u> .			
 Acknowledgment is made of a claim for foreign priority u a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 		r (f).	
Certified copies of the priority documents hav	e been received in Application	n No	
Copies of the certified copies of the priority do	ocuments have been received	in this national stage applicati	on from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file MENT of this application.	a reply complying with the req	uirements
 A SUBSTITUTE OATH OR DECLARATION must be subn INFORMAL PATENT APPLICATION (PTO-152) which give 	nitted. Note the attached EXA ves reason(s) why the oath or	MINER'S AMENDMENT or NO declaration is deficient.	OTICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") mu	st be submitted.		
(a) I including changes required by the Notice of Draftsper	son's Patent Drawing Review	(PTO-948) attached	
1) 🗌 hereto or 2) 📗 to Paper No./Mail Date		,	
(b) including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment or	in the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on th the header according to 37 CFI	e drawings in the front (not the li	back) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 	osit of BIOLOGICAL MATE FOR THE DEPOSIT OF BIO	RIAL must be submitted. N LOGICAL MATERIAL.	ote the
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	E There are		
 Notice of Preferences Cited (P10-692) Datice of Draftperson's Patent Drawing Review (PT0-948) 	<u> </u>	ormal Patent Application	
2. Notice of Dranperson's Fateric Drawing Review (F10-946)		mmary (PTO-413), ⁄Iail Date	
Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date	7. 🗌 Examiner's A	Amendment/Comment	
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛭 Examiner's S	Statement of Reasons for Allov	vance
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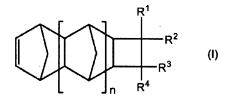
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REASONS FOR ALLOWANCE

1. The following is an examiner's statement of reasons for allowance: The claimed invention is drawn to the following:

A copolymer, a photoresist and a coated substrate comprising a substrate wherein the following copolymer is claimed:

(Previously Presented) A copolymer comprising a repeat unit derived from
 (a)at least one repeat unit derived from an ethylenically unsaturated
 compound having at least one fluorine atom covalently attached to an
 ethylenically unsaturated carbon atom; and
 (b)at least one repeat unit derived from an ethylenically unsaturated
 compound having the structure:



wherein n is 0, 1, or 2;

 R^1 , R^2 , R^3 and R^4 are independently H, OR^5 , halogen, alkyl or alkoxy of 1 to 10 carbon atoms, optionally substituted by halogen or ether oxygens, Y, $C(R_f)OR^5$, R^6Y or OR^6Y :

Y is COZ or SO₂Z;

R⁵ is hydrogen or an acid-labile protecting group;

 R_f and R_f are the same or different fluoroalkyl groups of 1 to 10 carbon atoms or taken together are $(CF_2)_m$ where m is 2 to 10;

 ${\sf R}^6$ is an alkylene group of 1 to 20 carbon atoms, optionally substituted by halogen or ether oxygen;

Z is OH, halogen, or OR7; and

 R^7 is an alkyl group of 1 to 20 carbon atoms, with the proviso that at least one of R^1 , R^2 , R^3 and R^4 is Y, OR^5 , $C(R_f)(R_f^4)OR^5$, R^6 Y or OR^6 Y, and the proviso that if R^1 (or R^3) is OH, R^2 (or R^4) is not OH or halogen.

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none of the prior art references of record disclose or anticipate the recited copolymer, a photoresist composition and a coated substrate comprising said copolymer having a structure of formula (I).

Accordingly, claims 1-45 are seen as allowable and passed to issue.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

2. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Examiner Chu whose telephone number is (571) 272-1329. The examiner can normally be reached on Monday - Friday from 9:30 am to 6:00 pm.

If attempts to reach the Examiner by telephone are unsuccessful, the Examiner's supervisor, Cynthia Kelly, can be reached on (571) 272-1526

The fax phone number for the USPTO is (571) 273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PMR only. For more information about the PAIR

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system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

ohn S. Chu

Primary Examiner, Group 1700

J.Chu April 30, 2007